

ABSTRACT

Provided are a sputtering target and a method for manufacturing the same, which can reduce generation of particles and improve a production yield in a deposition step of a magnetic thin film. The sputtering target includes Fe-Pt-based alloy phases and non-magnetic phases, wherein the sputtering target contains from 1 to 50 at% of C in an atomic number ratio, and has a diffraction peak derived from diamond as measured by XRD.